Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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ATTORNEY'S DKT NO.	APPLICATION NO.	
005950-739	10/720,673	
APPLICANT		
O'Rear et al.		
FILING DATE	GROUP	
11/25/2003	1754	

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\$			U.S. PATENT DOC	UMENTS	<u></u> -			
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. SEND TO: Assistant Commissioner for Patents, Washington, D.C. 20231.

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Examiner Initials	item (book,	, magazine, journa	al, serial, symposium, c publisher, city and/or c	atalog, etc.), di	ate, page	(s), volume-issue numb	er(s),	
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